

Akihiro Suzuki

List of Publications by Year in descending order

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papers

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citing authors

#	ARTICLE	IF	CITATIONS
1	Hydrogen passivation for reduction of SiO ₂ /Si interface state density using hydrocarbon-molecular-ion-implanted silicon wafers. Japanese Journal of Applied Physics, 2020, 59, 125502.	1.5	13
2	Reduction of Dark Current in CMOS Image Sensor Pixels Using Hydrocarbon-Molecular-Ion-Implanted Double Epitaxial Si Wafers. Sensors, 2020, 20, 6620.	3.8	9
3	Molecular and Atomic Hydrogen Diffusion Behavior by Reaction Kinetic Analysis in Projection Range of Hydrocarbon Molecular Ion for CMOS Image Sensors. Physica Status Solidi (A) Applications and Materials Science, 2019, 216, 1900175.	1.8	5
4	Fundamental Characteristics of Cyanide-Related Multielement Molecular Ion-Implanted Epitaxial Si Wafers for High-Performance CMOS Image Sensors. Physica Status Solidi (A) Applications and Materials Science, 2019, 216, 1900172.	1.8	5
5	Influence of oxygen on copper gettering in hydrocarbon molecular ion implanted region using atom probe tomography. Nuclear Instruments & Methods in Physics Research B, 2020, 478, 99-103.	1.4	4
6	Proximity gettering design of silicon wafers using silicon hydride and hydrocarbon mixture molecular ion implantation technique. Materials Science in Semiconductor Processing, 2021, 135, 106063.	4.0	3
7	Hydrogen diffusion behavior in CH ₂ P-molecular-ion-implanted silicon wafers for CMOS image sensors. Materials Science in Semiconductor Processing, 2022, 137, 106211.	4.0	1
8	Effect of ramping up rate on end of range defect in multielement molecular-ion (CH ₃ O)-implanted silicon wafers. Japanese Journal of Applied Physics, 2019, 58, 121002.	1.5	1
9	Photoemission Spectroscopy Study on Hydrogen Termination Effect on SiO ₂ /Si Structure Fabricated Using H ⁺ -Implanted Si Substrate. Journal of the Electrochemical Society, 2020, 167, 127505.	2.9	1
10	In Situ Transmission Electron Microscopy Study of Shrinkage Kinetics of CH ₄ N-Molecular-Ion-Implantation-Induced Extended Defects. Journal of the Electrochemical Society, 2022, 169, 047521.	2.9	1